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DC Characteristics of a MESFET

This model is licensed under the COMSOL Software License Agreement 6.0. All trademarks are the property of their respective owners. See www.comsol.com/trademarks. This model compares the current-voltage characteristics of a MESFET using the majority carrier only formulation.

Introduction

MOSFETs and MESFETs (metal-semiconductor field-effect transistor) work very similarly. In a MESFET, the gate forms a rectifying junction that controls the opening of the channel by varying the depletion width of the junction.

In this model we simulate the response of a n-doped GaAs MESFET to different drain and gate voltages. For a n-doped material the electron concentration is expected to be orders of magnitude larger than the hole concentration. Accordingly, it is possible to use the majority carrier option to compute an accurate solution with less degrees of freedom then it would normally be needed using the electrons and holes formulation.

Model Definition

The model compares the effect of the carrier formulation on the solution of a 2D MESFET biased with different gate (0, 1, and 2 V) and drain (from 0 to 10 V) voltages.

The geometry is composed of a block of 4 by $0.5 \,\mu\text{m}$. The Schottky contact (gate) has a length of 1 μm . The source (top left) and drain (top right) have both a length of $0.5 \,\mu\text{m}$. Figure 1 shows the model's geometry.



Figure 1: Geometry of the modeled MESFET.

Results and Discussion

Figure 2 plots the drain current as a function of the drain voltage for both studies (electrons and holes and majority carrier only). The result is identical. Note that the number of degrees of freedom used for the first study (electrons and holes) is 1.5 times larger than the number of degrees of freedom used for the second study (majority carrier only).



Figure 2: Drain current as a function of the drain voltage for the electrons and holes and for the majority carrier only (asterisk).

Application Library path: Semiconductor_Module/Transistors/mesfet

Modeling Instructions

From the File menu, choose New.

NEW

In the New window, click 🙆 Model Wizard.

MODEL WIZARD

- I In the Model Wizard window, click 🤬 2D.
- 2 In the Select Physics tree, select Semiconductor>Semiconductor (semi).
- 3 Click Add.
- 4 Click M Done.

GLOBAL DEFINITIONS

Parameters 1

I In the Model Builder window, under Global Definitions click Parameters I.

2 In the Settings window for Parameters, locate the Parameters section.

3 In the table, enter the following settings:

Name	Expression	Value	Description
L	1[um]	IE-6 m	Gate length
Wd	4[um]	4E-6 m	Device width
Hd	0.5[um]	5E-7 m	Device height
Ws	1[um]	IE-6 m	Source width
Wdd	1[um]	IE-6 m	Drain width
Vg	0[V]	0 V	Gate voltage
Vd	0[V]	0 V	Drain voltage
Vs	0[V]	0 V	Source voltage
Nd	1e16[1/cm^3]	1E22 1/m ³	Doping

GEOMETRY I

- I In the Model Builder window, under Component I (compl) click Geometry I.
- 2 In the Settings window for Geometry, locate the Units section.
- **3** From the **Length unit** list, choose **µm**.

Rectangle 1 (r1)

- I In the **Geometry** toolbar, click Rectangle.
- 2 In the Settings window for Rectangle, locate the Size and Shape section.
- **3** In the **Width** text field, type Wd.
- 4 In the **Height** text field, type Hd.
- 5 Locate the **Position** section. In the **x** text field, type -Wd/2.

Add points to define the source, drain and gate contacts.

Point I (ptl)

- I In the **Geometry** toolbar, click **Point**.
- 2 In the Settings window for Point, locate the Point section.
- **3** In the **x** text field, type -Wd/2+Ws/2 -L/2 L/2 Wd/2-Ws/2.
- 4 In the y text field, type Hd Hd Hd.
- 4 | DC CHARACTERISTICS OF A MESFET

5 Click 🟢 Build All Objects.

ADD MATERIAL

- I In the Home toolbar, click 🙀 Add Material to open the Add Material window.
- 2 Go to the Add Material window.
- 3 In the tree, select Semiconductors>GaAs Gallium Arsenide.
- 4 Click Add to Component in the window toolbar.
- 5 In the Home toolbar, click 🙀 Add Material to close the Add Material window.

SEMICONDUCTOR (SEMI)

Metal Contact 1

- I In the Model Builder window, under Component I (compl) right-click Semiconductor (semi) and choose Metal Contact.
- 2 In the Settings window for Metal Contact, locate the Contact Type section.
- 3 From the Type list, choose Ideal Schottky.
- 4 Select Boundary 5 only.
- **5** Locate the **Terminal** section. In the V_0 text field, type -Vg.

Metal Contact 2

- I In the Physics toolbar, click Boundaries and choose Metal Contact.
- **2** Select Boundary 3 only.
- 3 In the Settings window for Metal Contact, locate the Terminal section.
- **4** In the V_0 text field, type Vs.

Metal Contact 3

- I In the Physics toolbar, click Boundaries and choose Metal Contact.
- **2** Select Boundary 7 only.
- 3 In the Settings window for Metal Contact, locate the Terminal section.
- **4** In the V_0 text field, type Vd.

Analytic Doping Model I

- I In the Physics toolbar, click 🔵 Domains and choose Analytic Doping Model.
- **2** Select Domain 1 only.
- 3 In the Settings window for Analytic Doping Model, locate the Impurity section.
- 4 From the Impurity type list, choose Donor doping (n-type).

5 In the N_{D0} text field, type Nd.

Trap-Assisted Recombination 1

- I In the Physics toolbar, click 🔵 Domains and choose Trap-Assisted Recombination.
- **2** Select Domain 1 only.
- **3** In the Settings window for Trap-Assisted Recombination, locate the Shockley-Read-Hall Recombination section.
- **4** From the τ_n list, choose User defined. From the τ_p list, choose User defined.

Adjust the mesh slightly.

MESH I

Size

In the Model Builder window, under Component I (compl) right-click Mesh I and choose Edit Physics-Induced Sequence.

Size 2

- I In the Settings window for Size, locate the Element Size section.
- 2 From the Predefined list, choose Finer.
- 3 Click 📗 Build All.

ADD STUDY

- I In the Home toolbar, click $\stackrel{\text{vol}}{\longrightarrow}$ Add Study to open the Add Study window.
- 2 Go to the Add Study window.
- 3 Find the Studies subsection. In the Select Study tree, select General Studies>Stationary.
- 4 Click Add Study in the window toolbar.
- 5 In the Home toolbar, click Add Study to close the Add Study window.

STUDY I

Step 1: Stationary

Set up an auxiliary continuation sweep for the 'Vd' parameter.

- I In the Settings window for Stationary, click to expand the Study Extensions section.
- 2 Select the Auxiliary sweep check box.
- 3 Click + Add.

4 In the table, enter the following settings:

Parameter name	Parameter value list	Parameter unit
Vg (Gate voltage)		V

5 Click + Add.

6 In the table, enter the following settings:

Parameter name	Parameter value list	Parameter unit
Vg (Gate voltage)	0 1 2	V
Vd (Drain voltage)	range(0,1,10)	V

7 From the Sweep type list, choose All combinations.

8 From the Reuse solution from previous step list, choose Auto.

9 In the **Home** toolbar, click **= Compute**.

RESULTS

ID Plot Group 4

- I In the Home toolbar, click 💭 Add Plot Group and choose ID Plot Group.
- 2 In the Settings window for ID Plot Group, locate the Legend section.
- 3 From the Position list, choose Upper left.

Global I

- I Right-click ID Plot Group 4 and choose Global.
- 2 In the Settings window for Global, click Replace Expression in the upper-right corner of the y-Axis Data section. From the menu, choose Component I (compl)>Semiconductor> Terminals>semi.l0_3 - Terminal current - A.
- 3 Locate the y-Axis Data section. In the table, enter the following settings:

Expression	Unit	Description
semi.IO_3	Α	Electrons and holes

4 In the ID Plot Group 4 toolbar, click 💿 Plot.

ADD STUDY

- I In the Home toolbar, click $\stackrel{\sim}{\longrightarrow}$ Add Study to open the Add Study window.
- 2 Go to the Add Study window.
- 3 Find the Studies subsection. In the Select Study tree, select General Studies>Stationary.

- 4 Click Add Study in the window toolbar.
- 5 In the Home toolbar, click $\stackrel{\text{rob}}{\longrightarrow}$ Add Study to close the Add Study window.

STUDY 2

Step 1: Stationary

- I In the Settings window for Stationary, locate the Study Extensions section.
- **2** Select the **Auxiliary sweep** check box.
- 3 Click + Add.
- **4** In the table, enter the following settings:

Parameter name	Parameter value list	Parameter unit
Vg (Gate voltage)		V

5 Click + Add.

6 In the table, enter the following settings:

Parameter name	Parameter value list	Parameter unit
Vg (Gate voltage)	0 1 2	V
Vd (Drain voltage)	range(0,1,10)	V

7 From the Sweep type list, choose All combinations.

8 From the Reuse solution from previous step list, choose Auto.

SEMICONDUCTOR (SEMI)

I In the Model Builder window, under Component I (compl) click Semiconductor (semi).

2 In the Settings window for Semiconductor, locate the Model Properties section.

3 From the Solution list, choose Majority carriers only.

STUDY 2

In the **Home** toolbar, click **= Compute**.

RESULTS

Global 2

I In the Model Builder window, under Results>ID Plot Group 4 right-click Global I and choose Duplicate.

2 In the Settings window for Global, locate the Data section.

- 3 From the Dataset list, choose Study 2/Solution 2 (sol2).
- 4 Locate the y-Axis Data section. In the table, enter the following settings:

Expression	Unit	Description
semi.IO_3	А	Majority carriers only

5 Click to expand the Coloring and Style section. Find the Line markers subsection. From the Marker list, choose Asterisk.

ID Plot Group 4

- I In the Model Builder window, click ID Plot Group 4.
- 2 In the Settings window for ID Plot Group, locate the Plot Settings section.
- **3** Select the **x-axis label** check box.
- 4 In the associated text field, type Drain voltage (Vd).
- **5** Select the **y-axis label** check box.
- 6 In the associated text field, type Terminal current (A).
- 7 In the ID Plot Group 4 toolbar, click 💽 Plot.